



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of: )  
Inventors: Joshi et al. ) ATTORNEY FILE NO.:  
Serial No.: 10/812,591 ) SLA0786  
Filed: March 29, 2004 )  
Title: HIGH DENSITY PLASMA ) Examiner: Sarkar, Asok  
PROCESS FOR THE )  
FORMATION OF SILICON ) Customer No.: 55,286  
DIOXIDE ON SILICON ) Group Art: 2891  
CARBIDE SUBSTRATES ) Confirmation No.: 2314  
)

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Mail Stop Issue Fee  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

ISSUE FEE RESPONSE

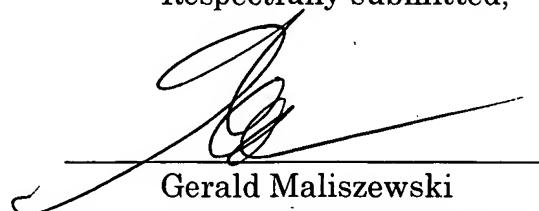
This paper is responsive to a Notice of Allowance mailed on  
June 8, 2006. Enclosed are:

two copies of the Issue Fee Transmittal form;  
6 sheets of Replacement drawings; and,  
a PTO-2038 form, in the amount of \$1709.

**REMARKS**

The Applicant neither expressly agrees nor disagrees with the stated reasons for the allowance of the claims.

Respectfully submitted,

  
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